



**675
HFCVD**



DIAMOND DEPOSITION REACTOR SYSTEM

- ✓ Enables synthesis of diamond films on a wide variety of materials.
- ✓ Polycrystalline diamond structure can be controlled to produce nanocrystalline or microcrystalline films, from 500 nm to 50 μm thick.
- ✓ Streamlined chamber frame and reduced facility footprint.
- ✓ Control rack as separate scalable component that can simultaneously control up to 4 independent reactor chambers.

System Specifications

Deposition Area	33 cm x 30 cm (13" x 12") per chamber
Power Consumption ...	35 kW max per chamber
Gas Control	3 MFC loops standard: H ₂ , CH ₄ , N ₂ / 2 additional gas loops available as options
Pressure Control	Operating range: 6 to 50 Torr / Downstream closed loop throttle valve control
Filament Power	30kW max: 200 Volts DC, 150 Amps
Footprint	Chamber frame 122 cm x 82 cm (48" x 32")
Height	190 cm (74.5") max
Weight	600 Kg (1320 lbs.)

